

## METHOD AND DEVICE FOR CHECKING LITHOGRAPHY DATA

### Abstract

Devices and methods are provided that include advantages such as the ability  
5 to identify sizes, shapes and locations of frequently unwanted additional features  
that occur as a result of photolithographic interference. The additional feature  
information is obtained through use of simulation methods with reduced processing  
time or solving a system of equations. This allows a user to quickly find  
information about additional feature printing before the features are printed, and  
10 before the reticle is made.